

Mass spectrometry and the usage @ PITZ

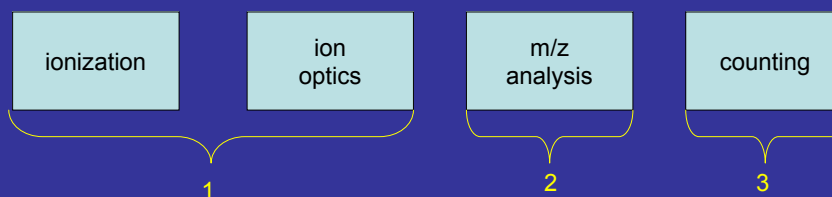
Sven Lederer
Technisches Seminar 29.05.2007

1. introduction
2. generation of gas phase ions
3. overview of mass spectrometry systems
4. residual gas analysis (RGA)
5. RGA @ PITZ
6. summary and outlook

If not special cited, than the pictures are taken from:
**“Mass Spectrometry of Inorganic, Coordination and
Organometallic Compounds”** - W. Henderson and
J.S. McIndoe

- Where can one use MS?
 - biology
 - chemistry
 - physics
 - in this talk Residual Gas Analysis (RGA)
 - environmental pollution
 - ...

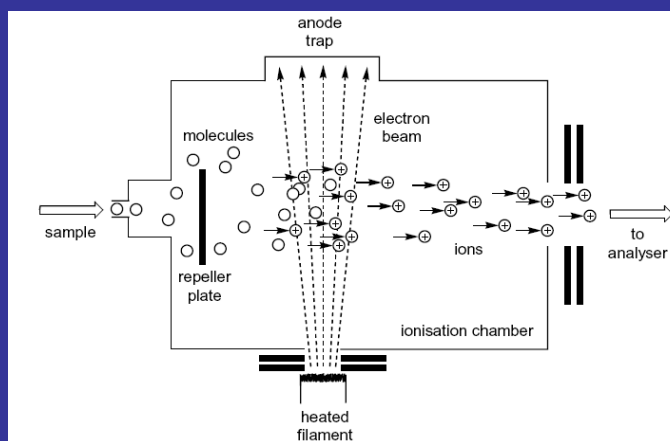
- What does a mass spectrometer (MS)?
1. generation of gas-phase ions
 2. separation to the mass-to-charge ratio
 3. counting



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2. generation of gas-phase ions

Electron ionization



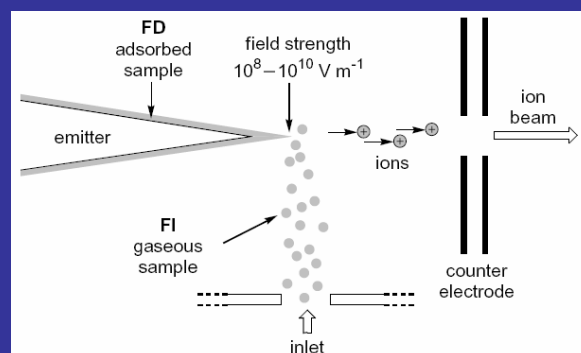
- typical electron energies below 100 eV
- used in most RGA's

2. generation of gas-phase ions

- strengths
 - established and very good understood
 - reproducible mass spectra
 - fragmentation can provide structural information

- weaknesses
 - sample must in gas phase

2. generation of gas-phase ions

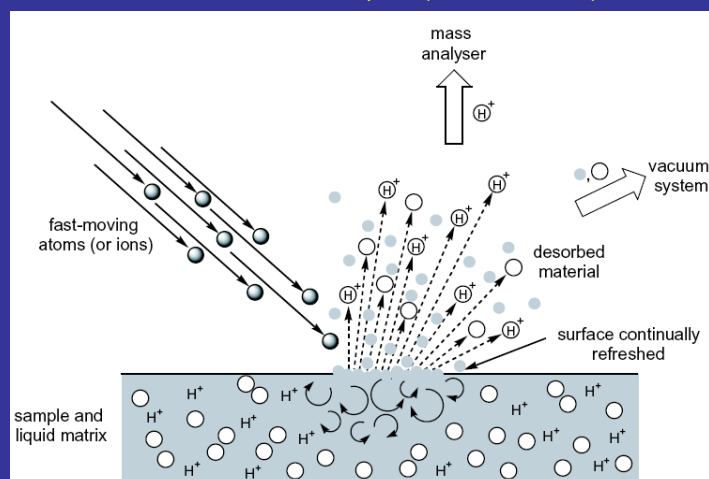


2. generation of gas-phase ions

- strengths
 - very soft ionization
 - nearly no chemical background
- weaknesses
 - preparation of the emitter
 - high fields often require use of sector MS

2. generation of gas-phase ions

used for solids ore liquids (matrix assisted)

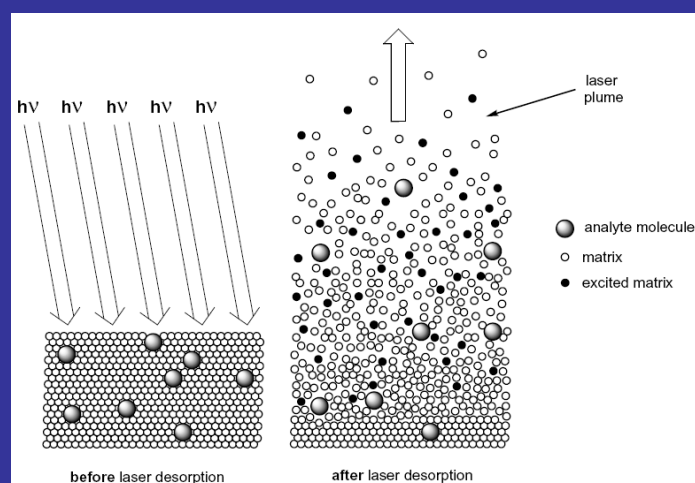


2. generation of gas-phase ions

- strengths
 - simple
 - also cold samples can be studied
 - high ion currents => good resolution
- weaknesses
 - high background
 - lower m/z dominated by matrix

2. generation of gas-phase ions

Matrix Assisted Laser Desorption Ionisation



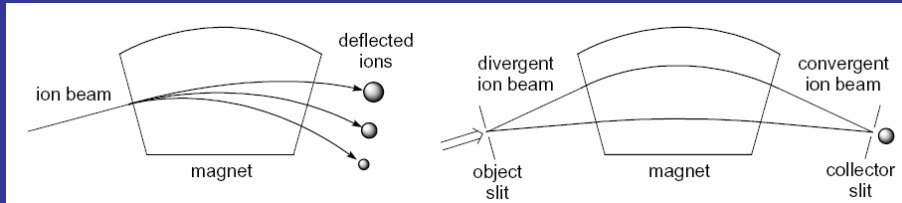
2. generation of gas-phase ions

- strengths
 - soft ionization poor fragmentation
 - rapid molecular weight determination
- weaknesses
 - MS/MS different
 - pulsed ionisation
 - spectra can depend on matrix

2. generation of gas-phase ions

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2. generation of gas-phase ions



ion source

$$E_{\text{kin}} = zV = \frac{mv^2}{2}$$

centrifugal and Lorentz force

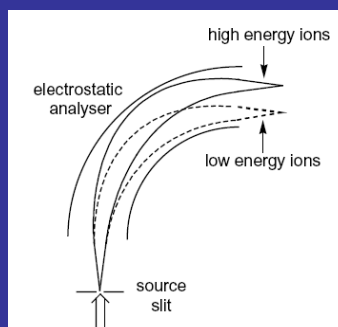
$$\frac{mv^2}{r} = B \cdot z \cdot v$$

$$\Rightarrow \frac{m}{z} = \frac{B^2 r^2}{2V}$$

directional focusing

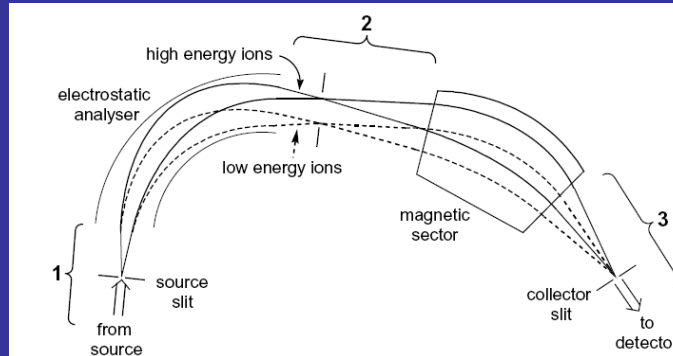
3. overview of mass spectrometry systems

A magnetic sector will focus ions with same m/z but different kinetic energy to different points. Therefore an electrostatic analyser is used before the magnetic sector.



3. overview of mass spectrometry systems

Sector MS



strengths:

- high resolution, sensitivity, and dynamic range

weaknesses:

- very large, expensive

TOF-MS

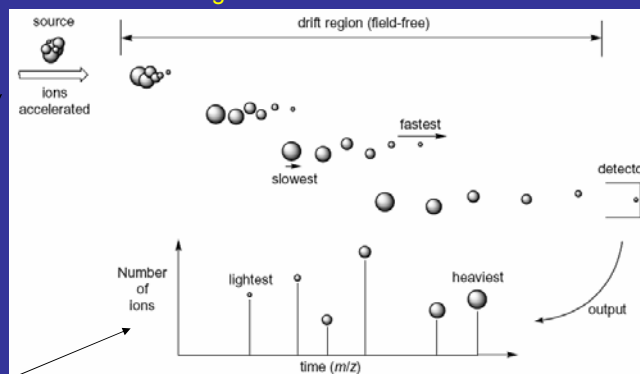
Time Of Flight MS: ions are accelerated by an electric field to the same kinetic energy
 → ions with different mass but same E_{kin} have different velocity v
 → heavier ions reach the detector after lighter ones

$$E_{kin} = U \cdot e \cdot z = \frac{m}{2} v^2$$

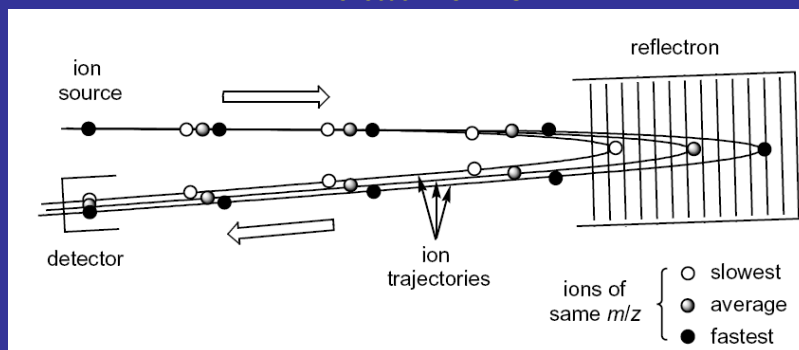
$$U \cdot e \cdot z = \frac{m}{2} \left(\frac{dx}{dt} \right)^2$$

$$\Rightarrow \frac{m}{z} = \frac{2 \cdot e \cdot U \cdot dt^2}{dx^2}$$

$$\Rightarrow \frac{m}{z} = \text{const.} \cdot dt^2$$



reflection TOF-MS

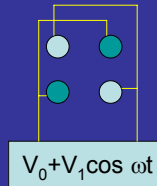
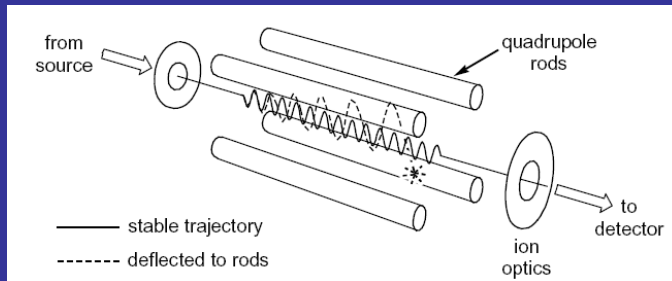


In a TOF-MS nearly all ions have same kin. energy. To ensure that really all ions with the same m/z ratio arrive at the same time at the detector an electronic ion mirror is used. The different kinetic energies are compensated by the different penetration depths. This provides an increase in resolution of the TOF-MS

3. overview of mass spectrometry systems

- strengths
 - unlimited mass
 - simplicity
 - no scanning necessary (detects all at once)
 - high transmission
- weaknesses
 - requires pulsed ionization or beam switching
 - high vacuum conditions required

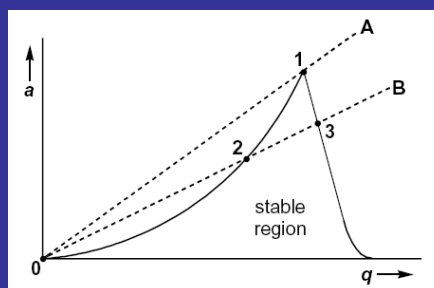
3. overview of mass spectrometry systems



$$\frac{m}{z} = \text{const.} \frac{V_1}{\omega^2}$$

For constant ω (typically some MHz) a mass scan is performed by changing V_1 . The precision depends on the ratio V_0/V_1 so that V_0 is changed together with V_1 .

stability diagram ($a \sim V_0, q \sim V_1$)



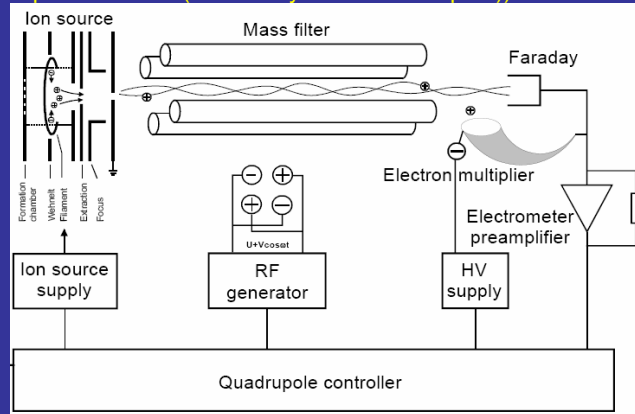
- strengths
 - compact
 - simplicity
 - fast scanning
 - mass spectra good reproducible
- weaknesses
 - resolution
 - not suited for pulsed ionization methods

MS	Price	Size	Resolution	Mass range
Sector	+	+	++	++
Quadrupole	+++	+++	+	+
TOF	++	++	++	+++

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5. RGA @ PITZ

- RGA's can provide information on:
 - residual gasses
 - air leaks in vacuum systems
 - Helium leaks especially in Helium leak tests
 - compositions of processes
 - impurities in process gasses

A residual gas analyser measures the partial pressures of individual masses in a gas mixture (vacuum). The sum of all partial pressures is the total pressure, which one can also measure with a vacuum gauge or an ion getter pump. Common systems consists of an ion source, a Quadrupole analyser, and an counter (Faraday cup and/or SEE (secondary electron multiplier)).



MS Basics M. Mueller

4. residual gas analysis (RGA)

Calculating the partial pressures P_A from measured currents I_{AB} :

$$P_A = \frac{FF_{N28}}{FF_{AB}XF_{AB}TF_BDF_{AB}G \cdot S} I_{AB} \quad \text{from INFICON LEYBOLD}$$

Analyser factors:

G: gain of the SEE or 1 for FC

S: sensitivity for pure Nitrogen

DF_{AB} : detection factor, 1 for FC and for SEE dependent on ion mass and the chemical nature, measured relative to the reference gas (usual Nitrogen)

TF_B : transmission factor, fractions of ions passing through the quadrupole relative to nitrogen $TF_B = 28/M$

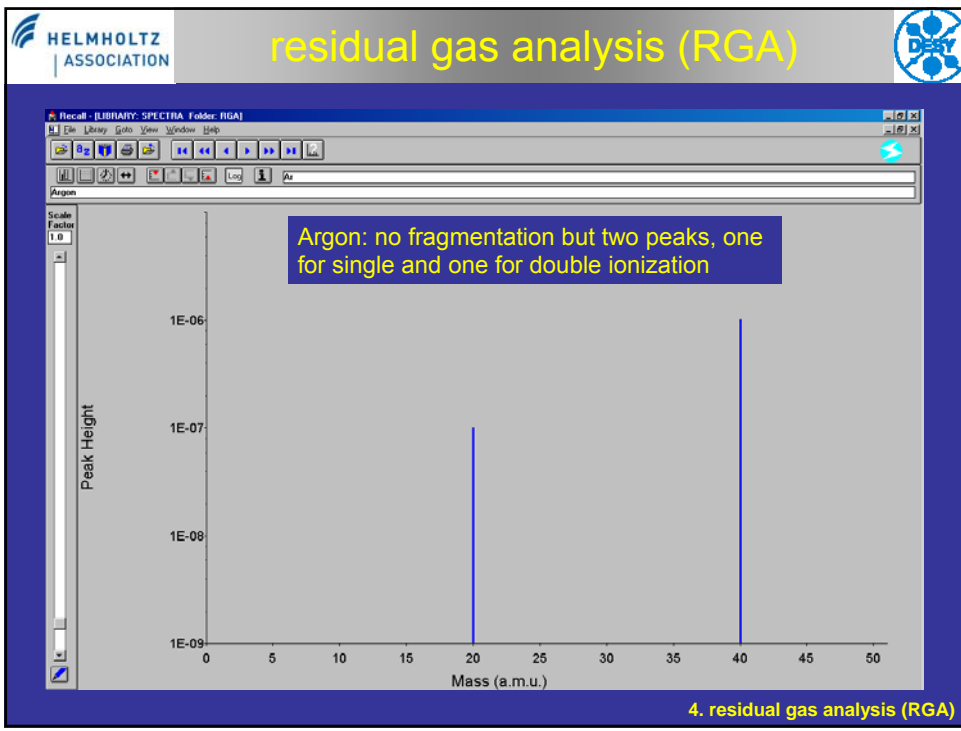
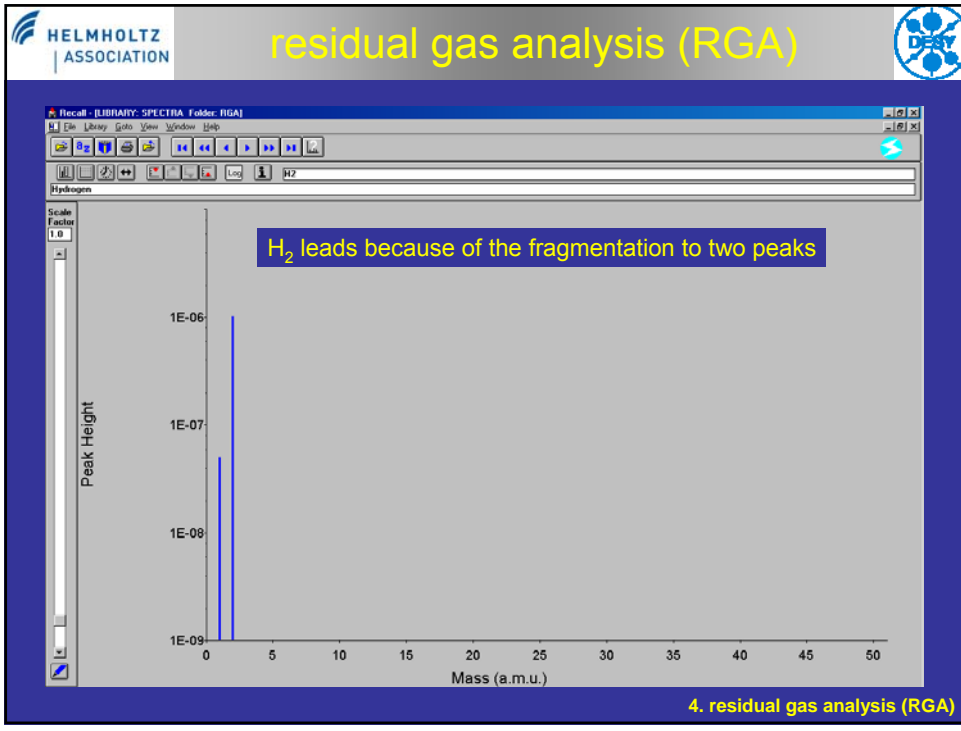
Material factors

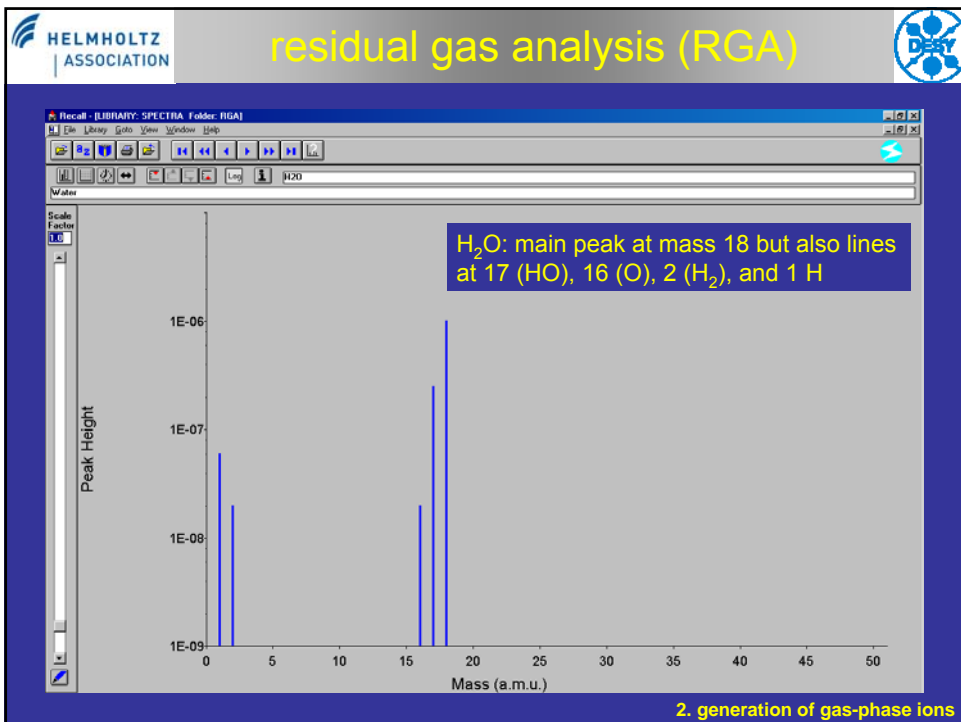
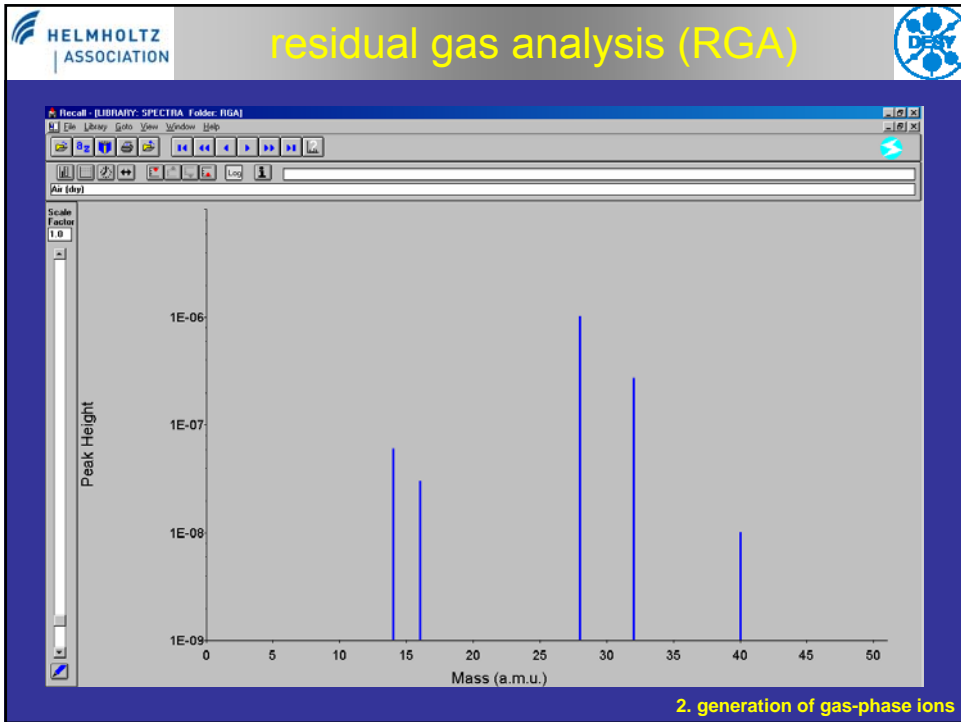
FF: fragmentation factors, FFN28 is the FF

XF: ionization probability

So the calculation of the partial pressure crucially depends on the chemical element itself and how the analyser can handle this element

4. residual gas analysis (RGA)





AMU	ION(S)	SOURCE(S)	AMU	ION(S)	SOURCE(S)
1	H	Hydrogen, Water, Acids, HY	19	F	Fluorine, Hydrofluoric acid, HL, Silicon tetrafluoride, PFK, PFTBA
2	H ₂	Hydrogen	20	HF	Hydrofluoric acid
	D	Deuterium		Ar	DI Argon
3	HD	Hydrogen – Deuterium		Ne	Neon
	He	³ Helium	22	Ne	²² Neon
4	He	Helium		CO ₂	DI Carbon dioxide
6	C	DI Carbon	24	C ₂	HL, HY
7	N	DI Nitrogen	25	C ₂ H	HY
8	O	DI Oxygen		CF ₂	HL, DI CF ₂
10	Ne	DI Neon	26	C ₂ H ₂	HY
11	Ne	DI ²² Neon		CN	Hydrogen cyanide
12	C	Carbon dioxide or monoxide, HY, HL	27	C ₂ H ₃	HY
13	CH	Methane, HY		HCN	Hydrogen cyanide
14	CH ₂	Methane, HY	28	C ₂ H ₄	HY
	N	Nitrogen, Ammonia		CO	Carbon dioxide or monoxide
15	CH ₃	Methane, HY		N ₂	Nitrogen, Air
	NH	Ammonia		Si	Silicon, Silicon tetrafluoride
16	CH ₄	Methane, HY	29	C ₂ H ₂	HY
	NH ₂	Ammonia		COH	Alcohol
	O	Oxygen, Carbon dioxide or monoxide, Water, Alcohol		N ₂	¹⁵ Nitrogen + ¹⁴ Nitrogen
17	NH ₃	Ammonia	30	C ₂ H ₆	HY
	OH	Water, Alcohol		COH ₂	Alcohol
18	H ₂ O	Water		N ₂	¹⁵ Nitrogen ₂
	Ar	DI ³⁶ Argon		NO	Nitrogen oxides

from
INFICON LEYBOLD

generation of gas-phase ions

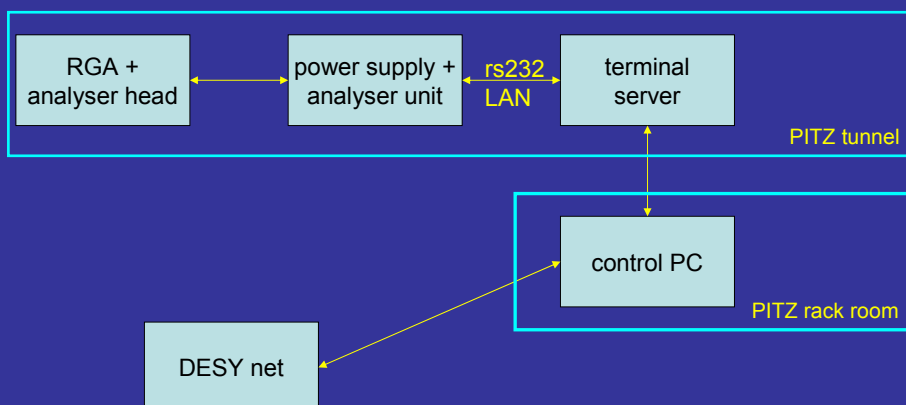
AMU	ION(S)	SOURCE(S)	AMU	ION(S)	SOURCE(S)
31	CH ₃ O	Alcohol	39	C ₃ H ₃	HY
	CF	HL, PFK, PFTBA	40	C ₃ H ₄	HY
	P	Phosphorus		Ar	Argon
32	CH ₂ OH	Alcohol	41	C ₃ H ₅	HY
	CHF	HL		C ₃ HO	Alcohol
	O ₂	Oxygen	42	C ₃ H ₆	HY
	S	Sulfur		C ₂ H ₂ O	Alcohol
33	SH	Hydrogen sulfide	43	C ₃ H ₇	HY
	S	³³ Sulfur		C ₂ H ₃ O	Alcohol, Acetone, Methyl Ethyl Ketone
	CH ₂ F	HL	44	C ₃ H ₈	HY
34	H ₂ S	Hydrogen sulfide		CO ₂	Carbon dioxide
	SH	Hydrogen- ³³ sulfide		N ₂ O	Nitrous oxide
	S	³⁴ Sulfur		CS	Carbon disulfide
	CH ₃ F	HL	45	C ₂ H ₅ O	Alcohol
35	H ₂ S	Hydrogen- ³³ sulfide	46	C ₃ H ₅ OH	Alcohol
	Cl	Chlorine, Hydrochloric acid, HL, Chlorobenzene, Carbon tetrachloride		NO ₂	Nitrogen dioxide
	OF	HL	47	CCl	Carbon tetrachloride, HL
36	H ₂ S	Hydrogen- ³⁴ sulfide		SiF	Silicon tetrafluoride
	HC1	Hydrochloric acid	48	CHCl	HL
	C ₃	HY		SO	Sulfur dioxide
	Ar	³⁶ Argon	49	CH ₂ C1	HL, Chlorobenzene
37	Cl	³⁷ Chlorine, HL, Hydrochloric acid, Chlorobenzene, Carbon tetrachloride		CC1	Carbon tetrachloride, HL
	C ₃ H	HY	50	CHC1	HL, Chlorobenzene
38	HC1	Hydrogen- ³⁷ chloride		CF ₂	HL, PFK, PFTBA
	C ₃ H ₂	HY		C ₄ H ₂	HY
	F ₂	HL, Fluorine		SO ₂	Sulfur dioxide

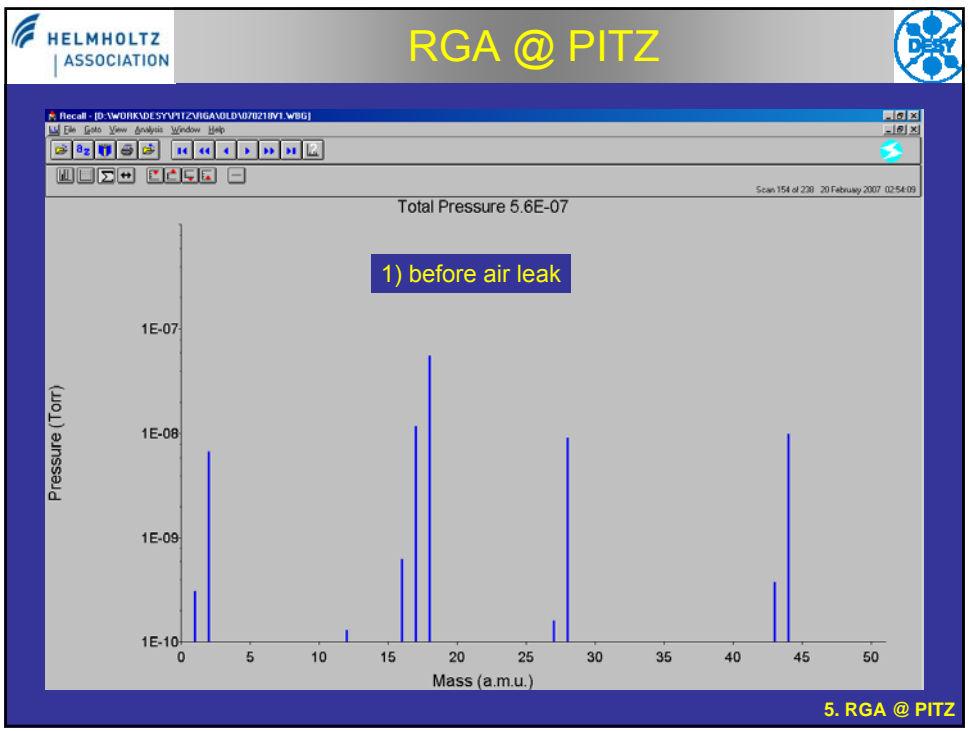
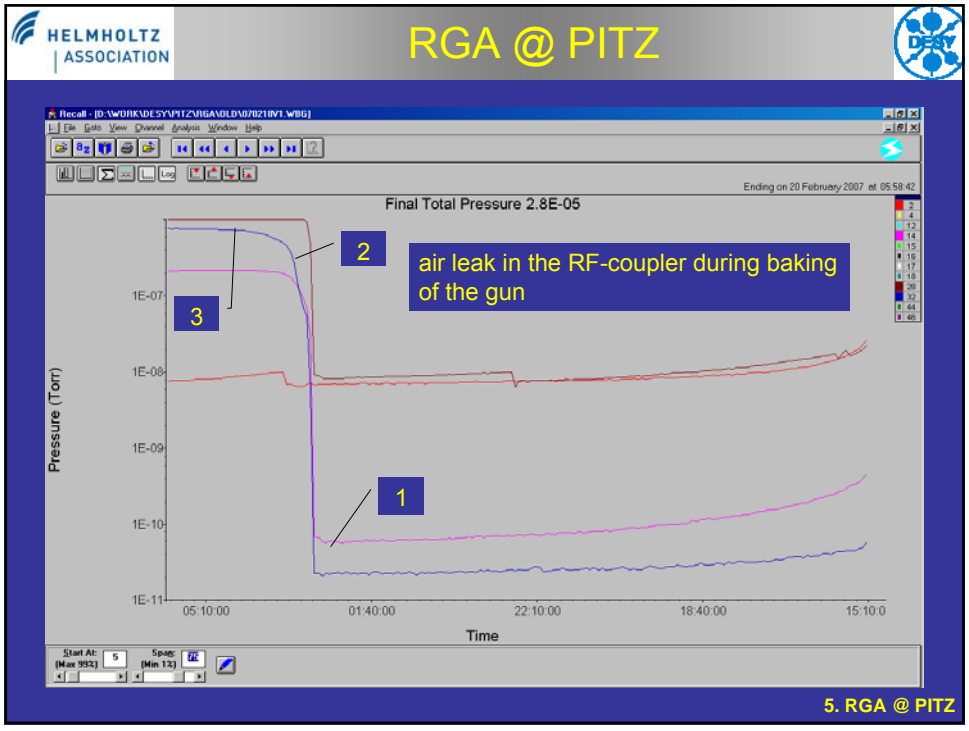
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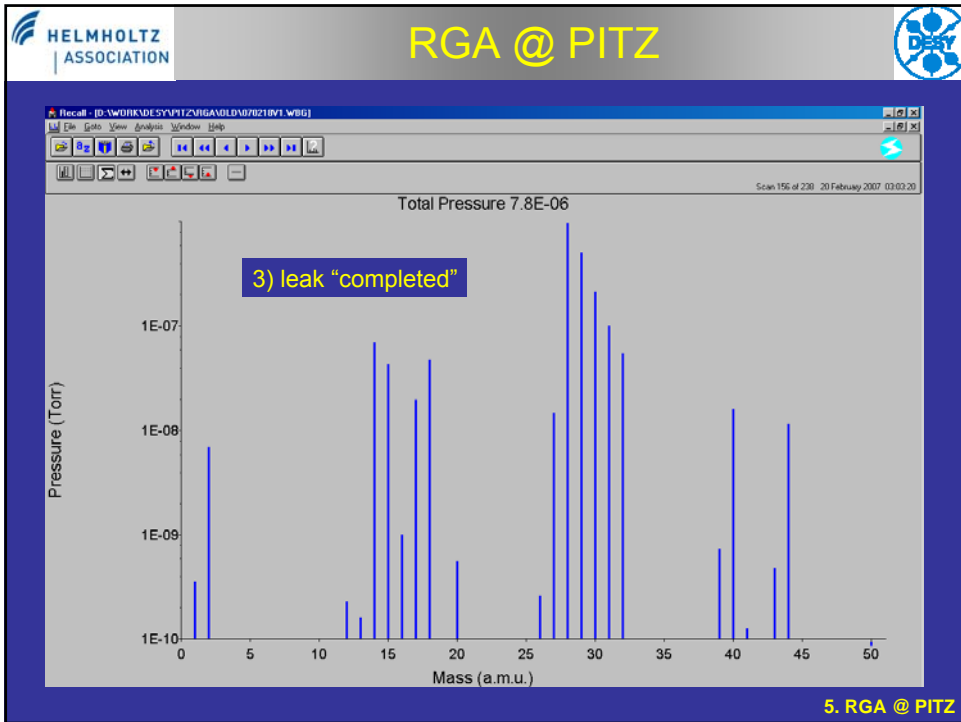
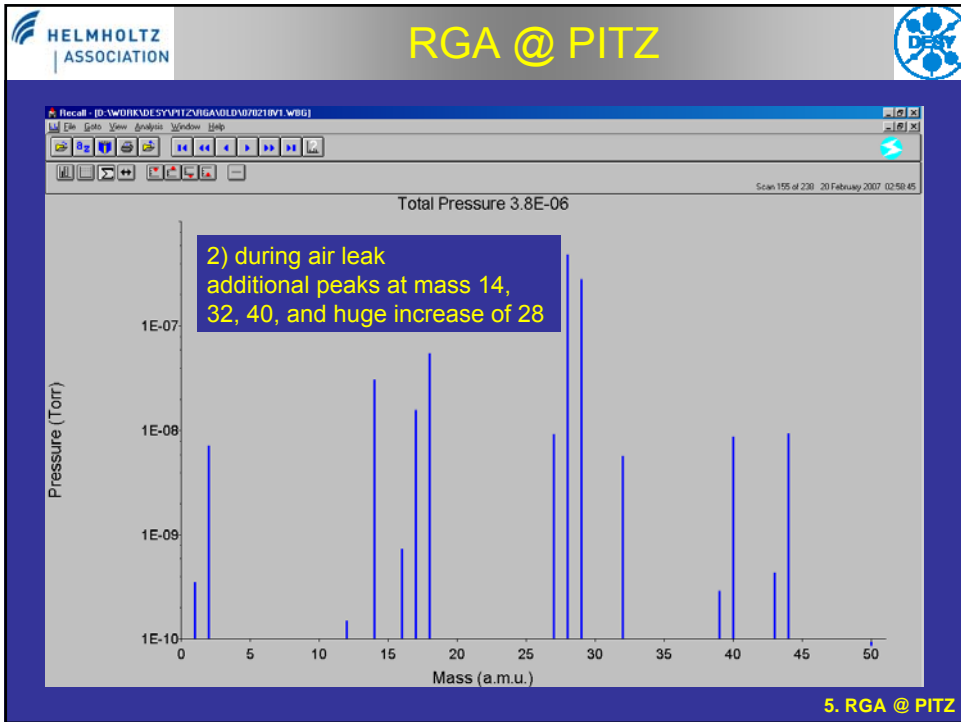
2. generation of gas-phase ions

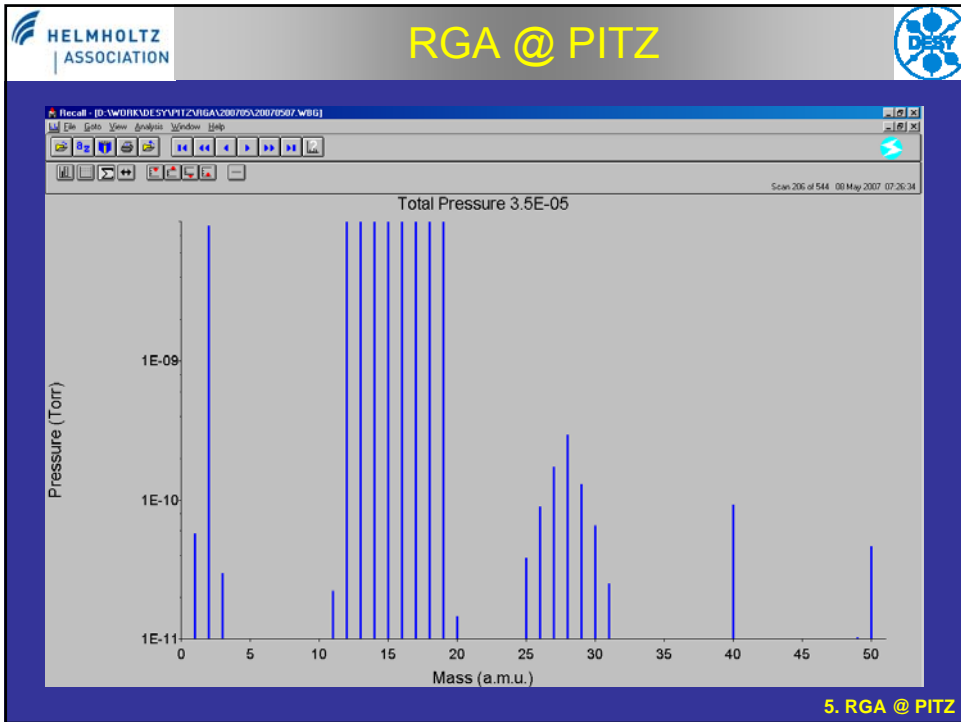
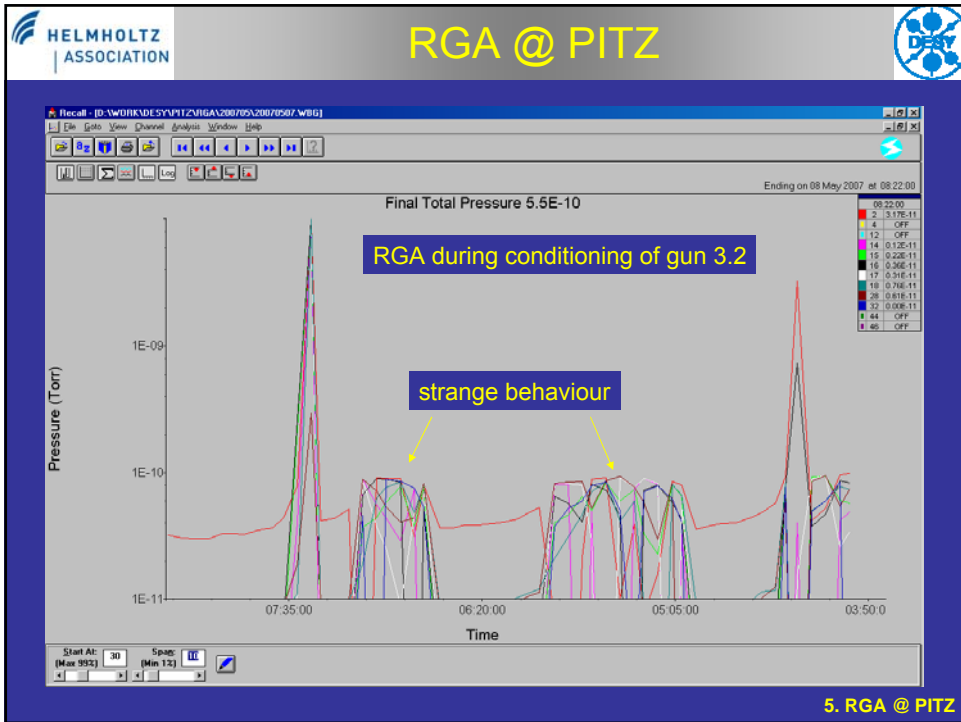
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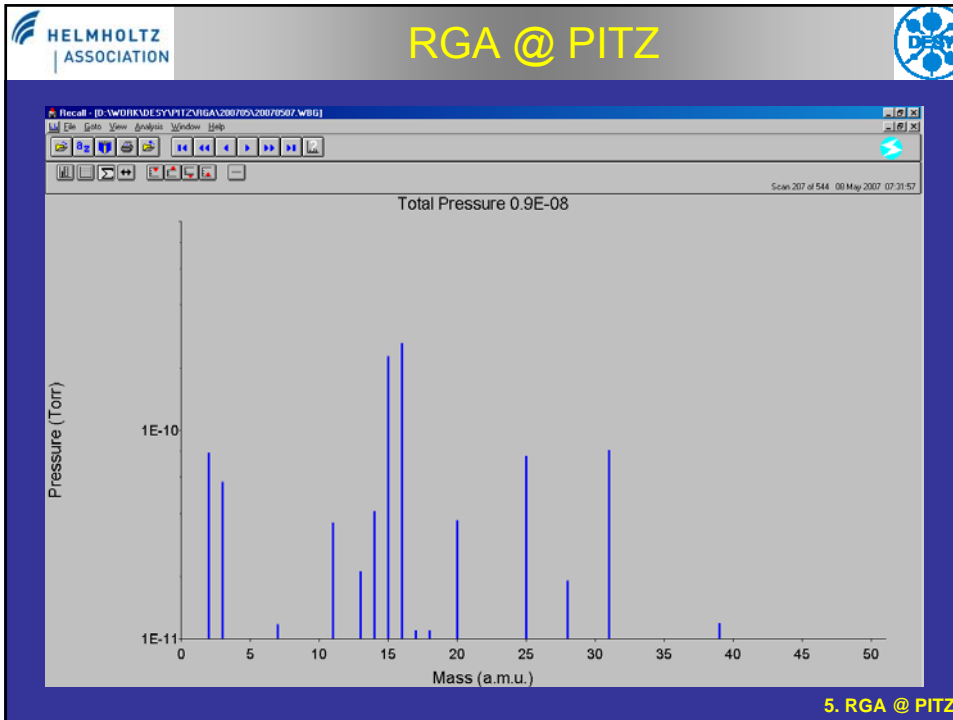
As RGA a Spectra Satellite LM61 (100 amu) is used.
The RGA is located near the PITZ RF-gun. The system needs 5 min. for measuring one spectrum from mass 1 to 50 (gun and coupler: Cu 64 amu).












- HELMHOLTZ ASSOCIATION summary and outlook 
- summary
 - MS systems and ionisation techniques were presented
 - description of special MS-topic RGA
 - introduction to the usage of RGA @ PITZ
 - outlook
 - understanding of the some times strange behaviour of the RGA @ PITZ
 - evaluation of the data taken during conditioning
 - new system
 - probably Pfeiffer QMS: consistency to system in vacuum lab, no complicate way of communication because of fibre connection
2. generation of gas-phase ions